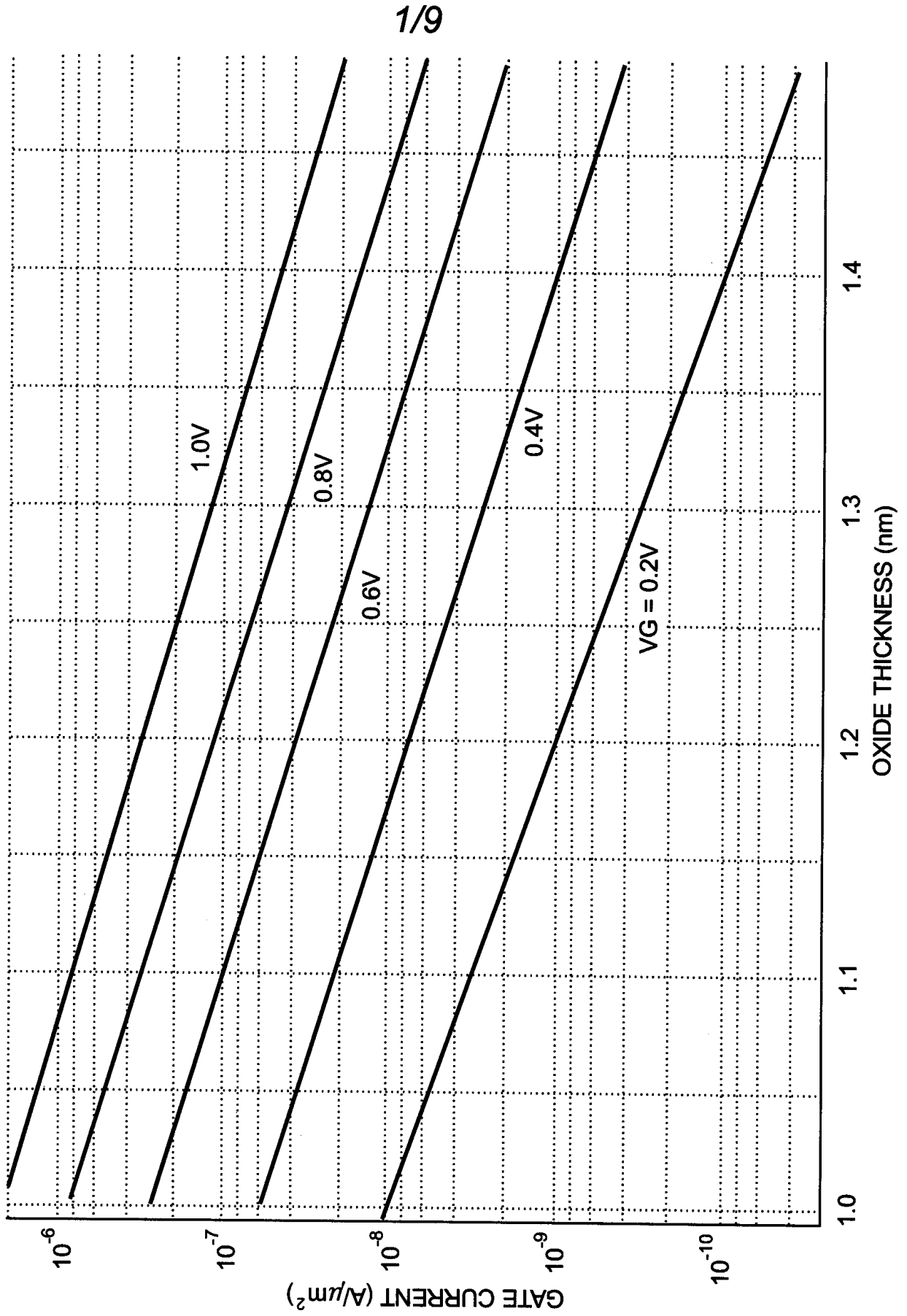
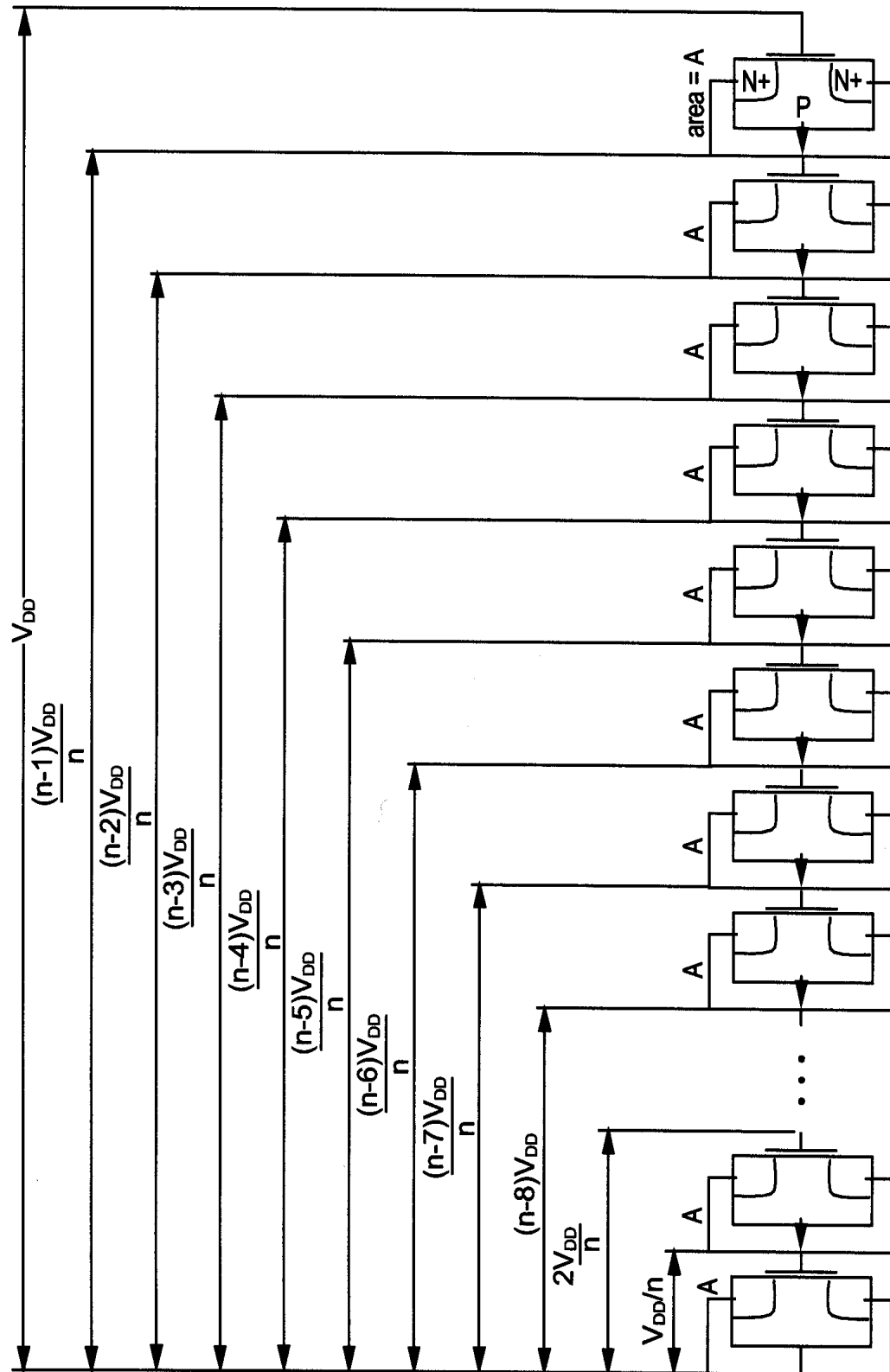


FIG. 1  
NFET GATE CURRENT VERSUS OXIDE THICKNESS



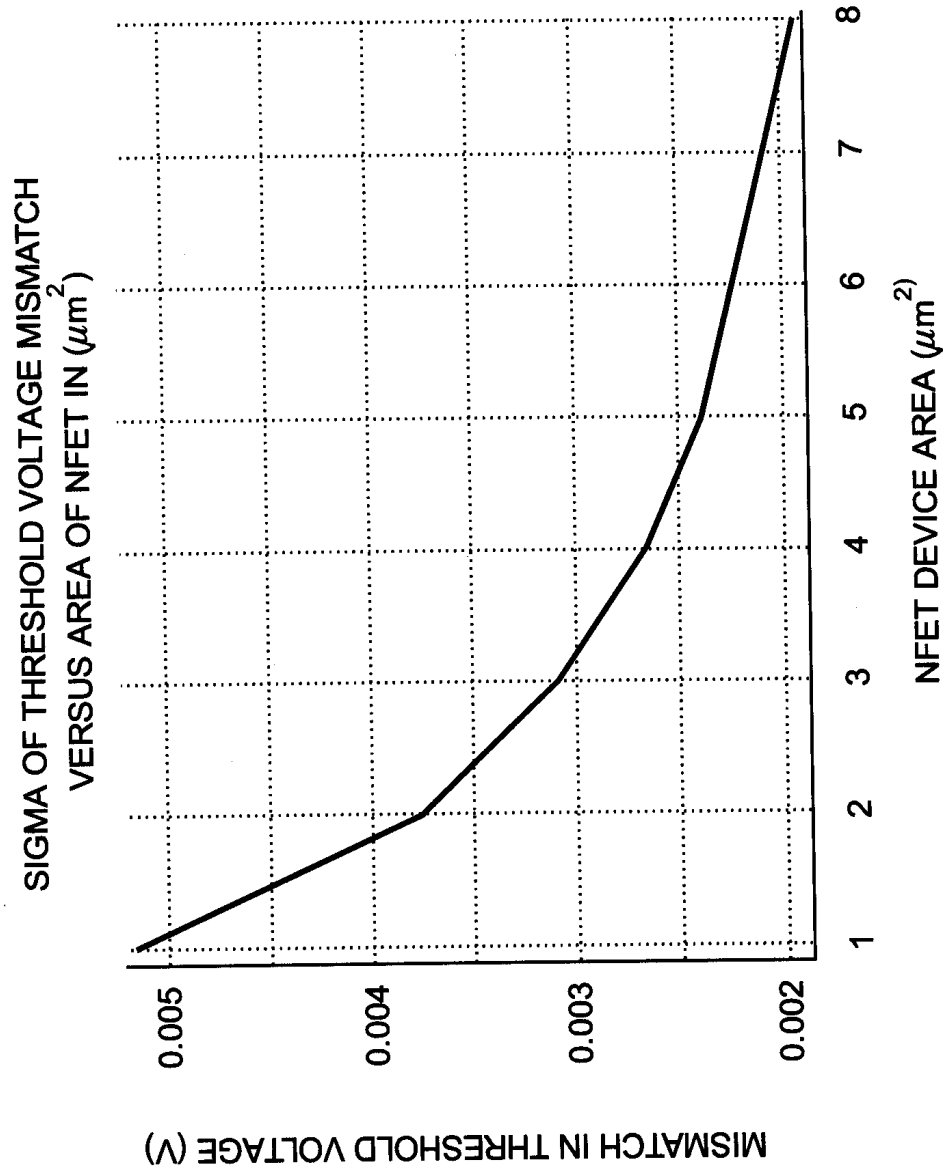
2/9

FIG. 2



3/9

FIG. 3



4/9

FIG. 4

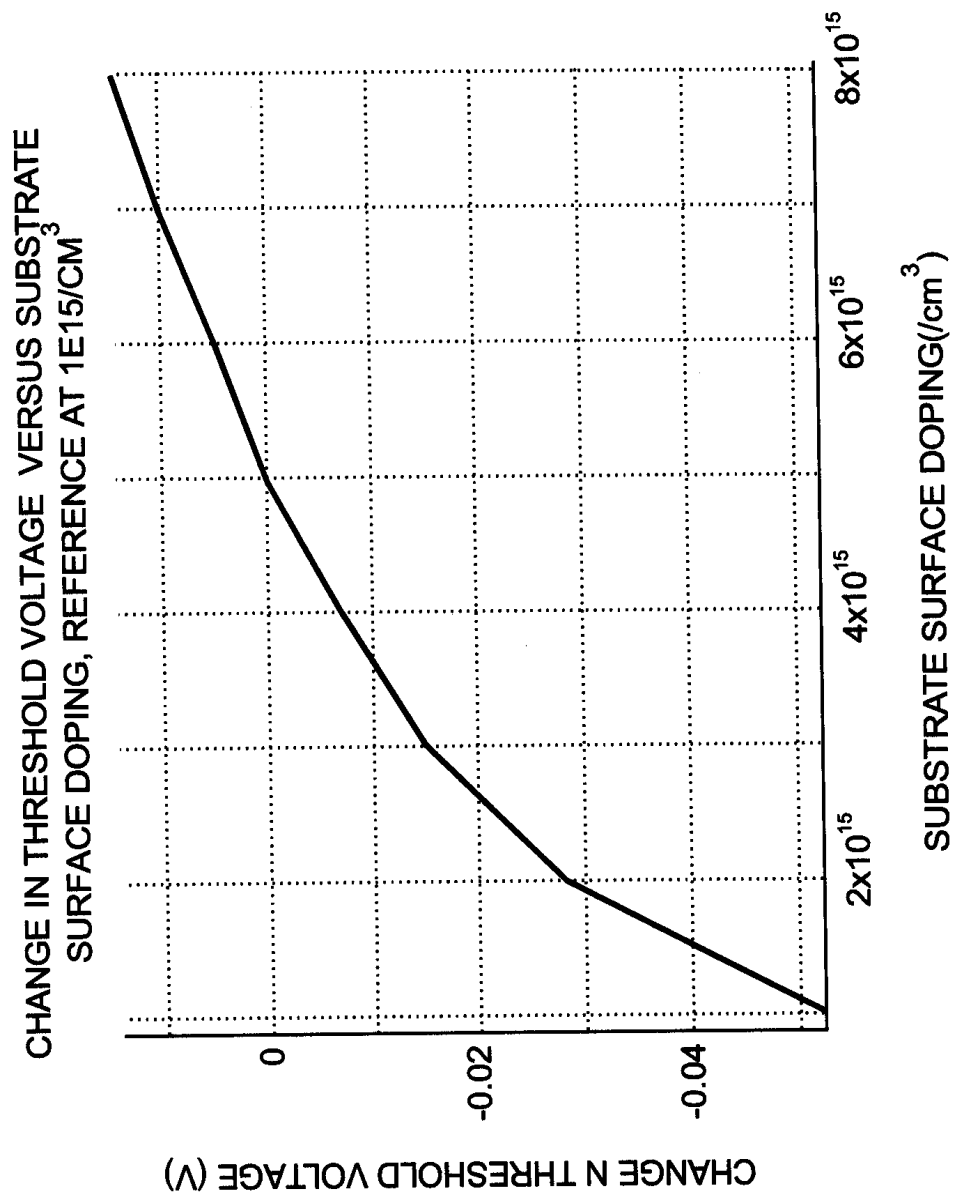


FIG. 5

EFFECT OF SUBSTRATE SURFACE DOPING ON  
NFET, GATE TUNNELING CURRENT

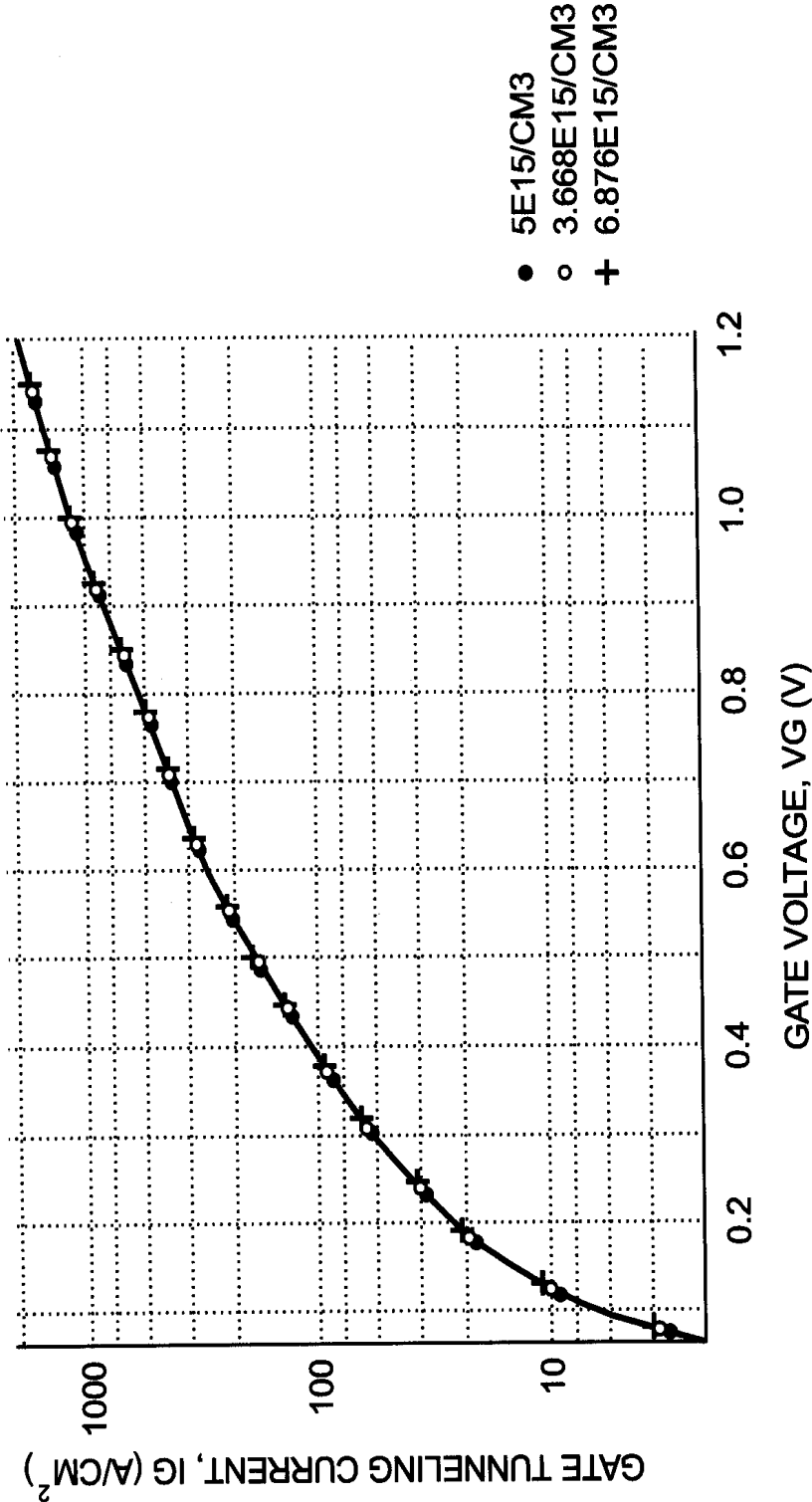


FIG. 6

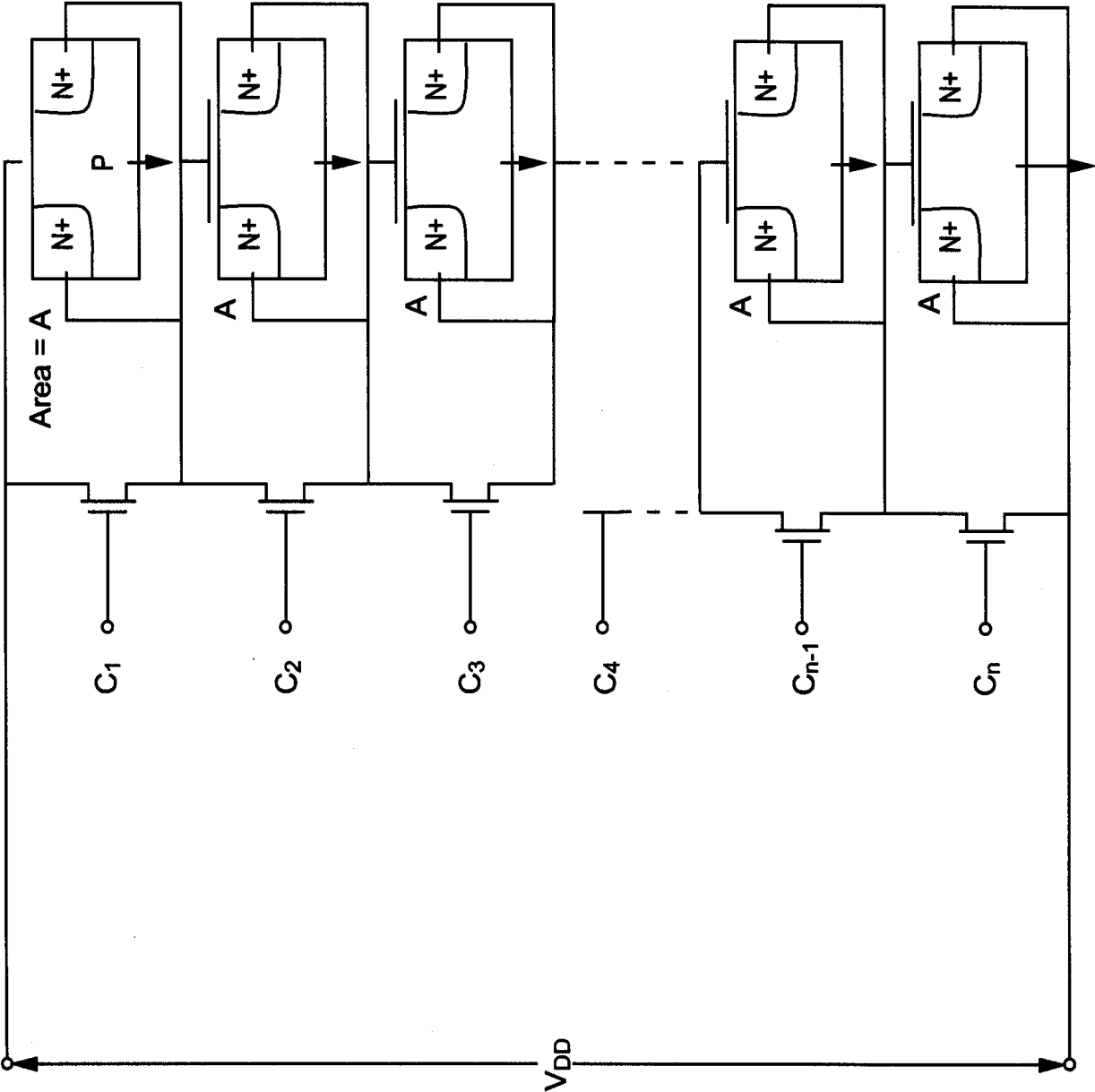


FIG. 7

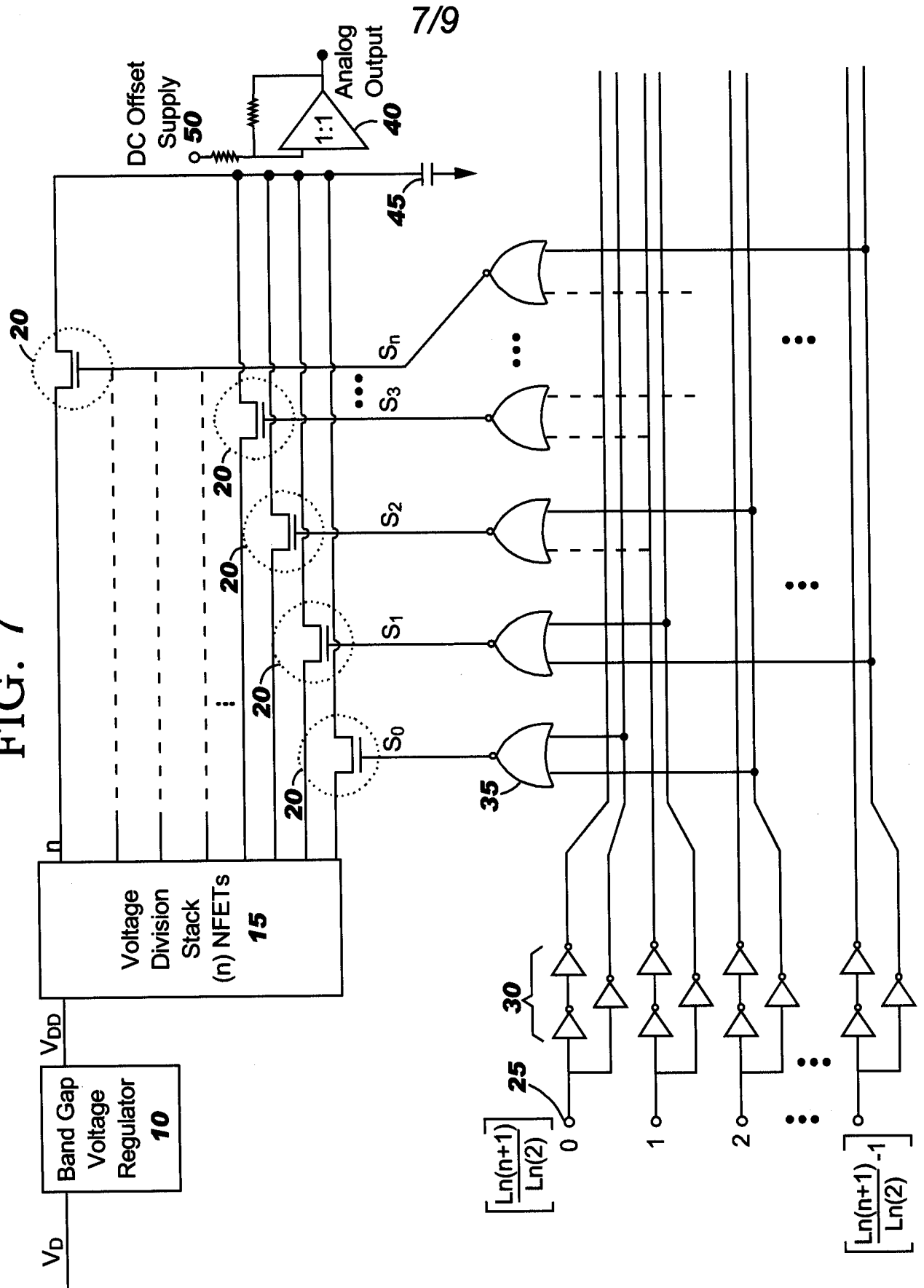
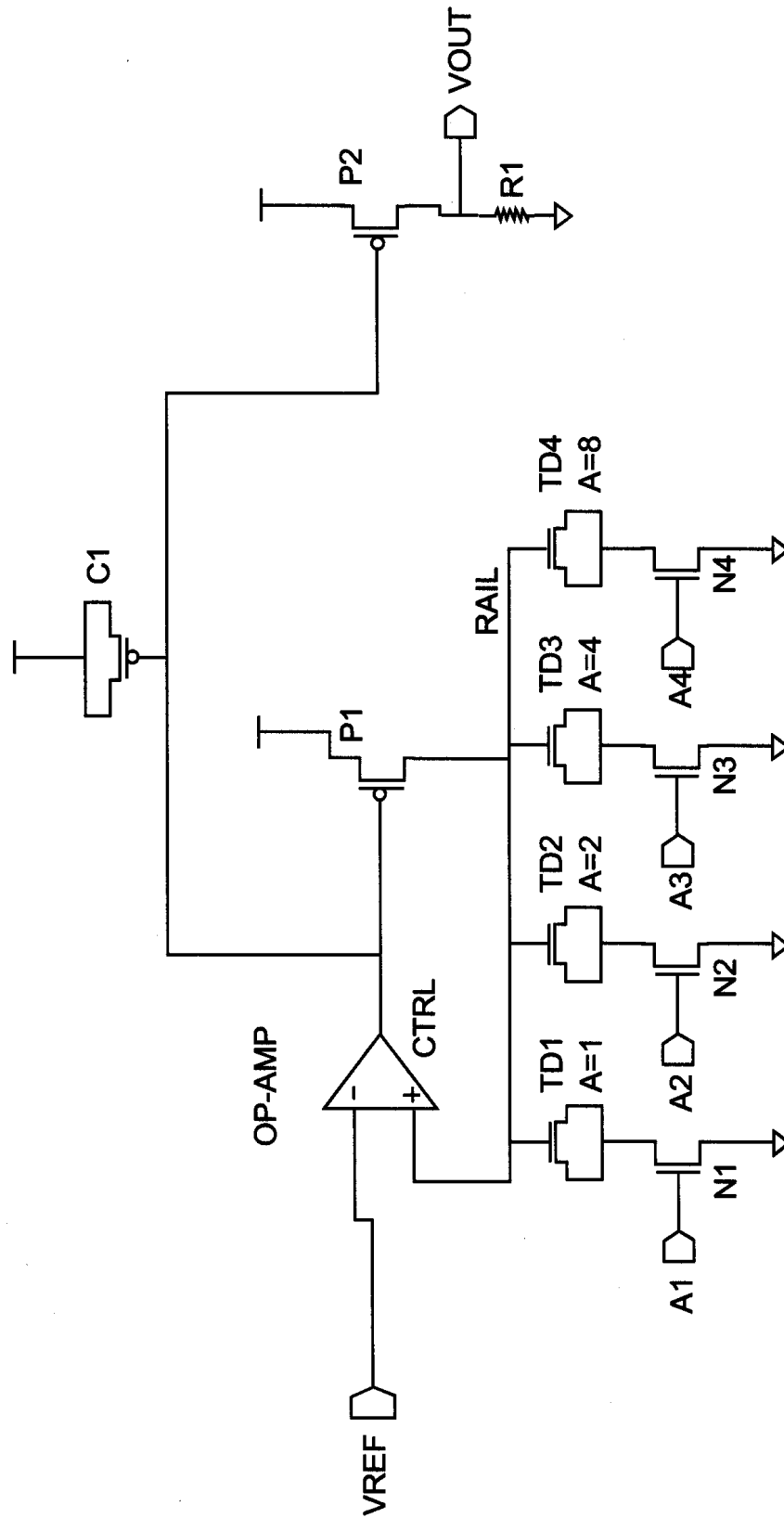


FIG. 8





9/9

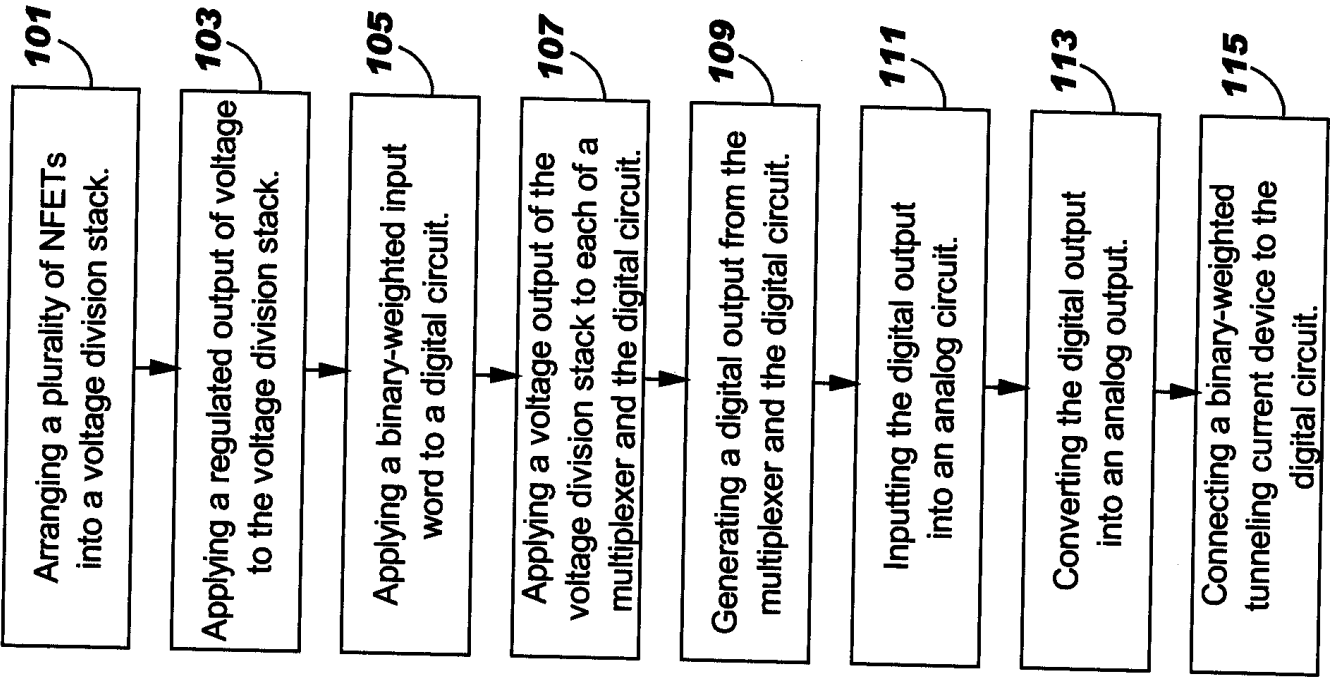


FIG. 9